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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/812,418	03/30/2004	Kerstin Mothes	543822005000	1266
71305 7550 03/31/2008 ESCHWEILER & ASSOCIATES LLC NATIONAL CITY BANK BUILDING			EXAMINER	
			SMITH, BRADLEY	
CLEVELAND	O, OH 44114		ART UNIT	PAPER NUMBER
			2891	
			NOTIFICATION DATE	DELIVERY MODE
			03/31/2008	ELECTRONIC

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Notice of the Office communication was sent electronically on above-indicated "Notification Date" to the following e-mail $\,$ address(es):

docketing@eschweilerlaw.com

Application No. Applicant(s) 10/812.418 MOTHES ET AL. Office Action Summary Examiner Art Unit Bradlev K. Smith 2891 -- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --Period for Reply A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS. WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION. Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). Status 1) Responsive to communication(s) filed on 03 December 2007. 2a) This action is FINAL. 2b) This action is non-final. 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213. Disposition of Claims 4) Claim(s) 1-6 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. 5) Claim(s) _____ is/are allowed. 6) Claim(s) 1-6 is/are rejected. 7) Claim(s) _____ is/are objected to. 8) Claim(s) _____ are subject to restriction and/or election requirement. Application Papers 9) The specification is objected to by the Examiner. 10) The drawing(s) filed on is/are; a) accepted or b) objected to by the Examiner. Applicant may not request that any objection to the drawing(s) be held in abevance. See 37 CFR 1.85(a). Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152. Priority under 35 U.S.C. § 119 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received.

1) Notice of References Cited (PTO-892)

Notice of Draftsperson's Patent Drawing Review (PTO-948)

Attachment(s)

Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____.

6) Other:

5) Notice of Informal Patent Application

Application/Control Number: 10/812,418

Art Unit: 2891

DETAILED ACTION

Claim Rejections - 35 USC § 112

The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

Claims 1-5 are rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the enablement requirement. The claim(s) contains subject matter which was not described in the specification in such a way as to enable one skilled in the art to which it pertains, or with which it is most nearly connected, to make and/or use the invention. The specification defines selective oxide deposition as:

An example of a selective oxide deposition process of this type is an ozone TEOS process with a high process pressure and a high ozone content. In this case, scarcely any oxide grows on the nitride mask 3.

Claims 1-5 disclose "selectively depositing a first insulation material only in the trench and not on the mask". This statement in claim 1 is not supported by the specification. According to the specification, at least some oxide grows on the mask.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-6 are rejected under 35 U.S.C. 102(b) as being anticipated by Ahn (US

2002/0072198). Regarding claims 1 and 6, Ahn disclose forming a mask on a substrate; forming

Application/Control Number: 10/812,418

Art Unit: 2891

at least one trench (121) in the substrate by using the mask; in the presence of the mask, selectively forming a first insulation material (129) only on the substrate in the trench to fill a lower part of the at least one trench in the substrate with the insulation material reducing the aspect ratio of the at least one trench mask; and applying a second insulation material (149) over an entire surface of the structure to fill the at least one trench in the substrate at least up to a top side of the mask (see figures 8 and 9). Regarding claim 2, Ahn disclose the substrate is silicon (100)[0030] the mask is silicon nitride [0030] and the first (129) and second (149) dielectric layers are silicon oxide. Regarding claim 3, Ahn disclose conditioning the dielectric layer [0035]. Regarding claim 4, Ahn disclose the second dielectric layer is formed by a HDP process [0038]. Regarding claim 5, Ahn disclose the second insulation material is planarized by CMP [0037].

Response to Arguments

Applicant's arguments filed 12/3/07 have been fully considered but they are not persuasive.

Regarding the applicant's allege that Ahn fails to teach the insulating material is deposited in the trench, but not on the mask. But the examiner would like to point out once again that there is no support in the specification for this claim limitation (see 112 1st paragraph rejection above).

With regards to claim 3, the applicant's allege that Ahn fails to disclose a conditioning process. The examiner would like to point out that Ahn disclose a curing process which would inherently compact the insulation layer, therefore Ahn discloses the conditioning process of claim 3.

Application/Control Number: 10/812,418

Art Unit: 2891

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Chen (US Patent 6,265,298) disclose curing SOG will compact the SOG (see column 3 lines 58-59).

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Bradley K. Smith whose telephone number is 571-272-1884. The examiner can normally be reached on 10-6.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Bill Baumeister can be reached on 571-272-1722. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Application/Control Number: 10/812,418 Page 5

Art Unit: 2891

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Bradley K Smith/ Primary Examiner, Art Unit 2891